

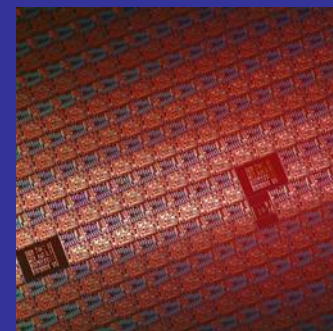


Accelerating the next technology revolution

Closing Remarks

iEUVi Mask TWG

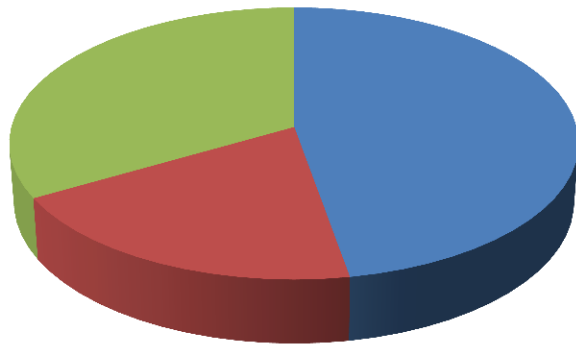
September 30, 2012, Brussels, Belgium



Mask TWG Participations 2009 - 2012

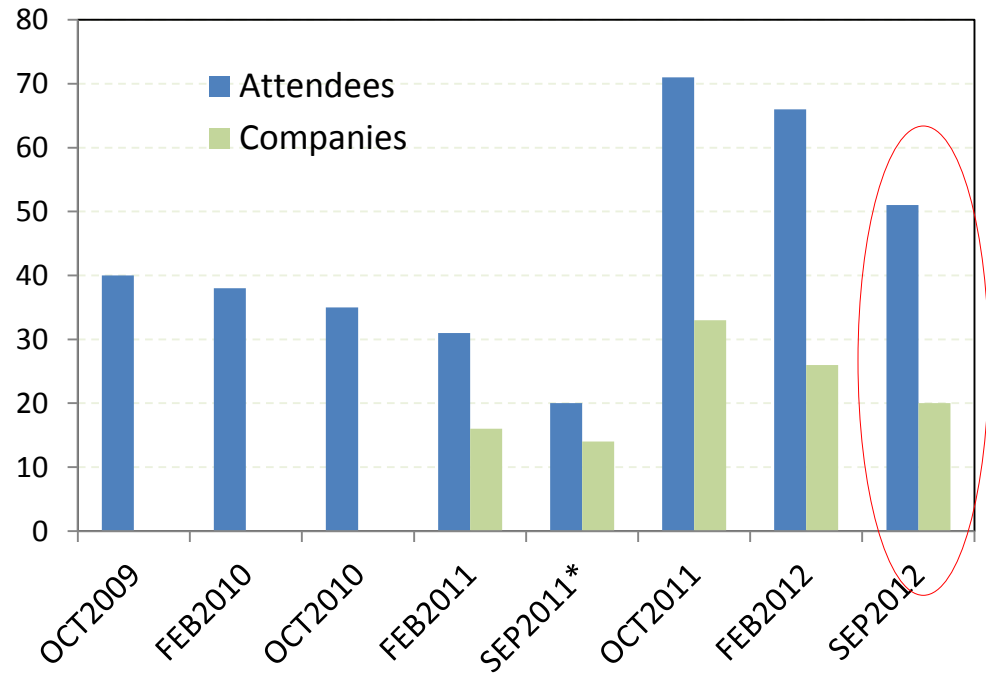


A total of 51 attended Sunday TWG (9/30), representing 20 companies or organizations



■ Asia-Pacific: 17
■ EU: 7
■ US: 12

Participating companies
by region (2009-2012)



*Special TWG held at BACUS

Attendance trend: total attendees
representing # of companies

Next IEUVI Mask TWG



- **Schedule: In conjunction with SPIE Lithography 2013, San Jose, CA**
- **We are listening to suggestions on topics and priorities.**
- **Other inputs are welcome, as well, such as meeting formats.**
- **Contact / Organizing Committee:**

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John Zimmerman – ASML

Ota Kazuya – Nikon

Markus Bender – AMTC

George Huang – UMC

Thank You!